

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Mark D. Owen, Bonnie A. Larson,
and Jozef Van Puymbroeck

Group Art Unit: 1742

Application No. 08/651,036

Filed: May 17, 1996

For: **METHOD EMPLOYING UV LASER PULSES OF VARIED
ENERGY DENSITY TO FORM DEPTHWISE SELF-LIMITING
BLIND VIAS IN MULTILAYERED TARGETS****DRAFT**

Date: May 15, 1998

Examiner: Gregory Mills

SUPPLEMENTAL AMENDMENTTO THE ASSISTANT
COMMISSIONER FOR PATENTS:

Following applicants' May 1, 1998 response to the April 3, 1998
Office action, please additionally amend the above-identified patent application as
follows.

In the Drawings:

Add Figs. 23 and 24.

In the Specification:

On page 8, line 16, after "invention.", add the following paragraph:

--Fig. 23 presents a table of Example 12 of parameters of laser pulses
employed to produce through-hole vias and blind vias, ^{blind via produced} by processing the organic
dielectric and the metal layers at different peak powers.

Fig. 24 presents a second table of Example 12, showing the conversion
of the original data into fluences and power densities by well-known laser
equations.--

On page 20, line 8, after "possible.", add the following paragraphs: